

ABSTRACT OF THE DISCLOSURE

An exposure apparatus includes a mask on which a transfer pattern is formed and a mask scanning unit for 5 scanning the mask, a wafer coated with a photosensitive material and a wafer stage scanning unit for scanning a wafer stage on which the wafer is mounted, a transfer unit for supplying/recovering the wafer to/from the wafer stage, and a positioning unit for positioning the 10 wafer and the mask, sequentially exposes the transfer pattern on the wafer by illuminating part of the transfer pattern with a light beam emitted from a light source through an illumination optical system and synchronously scanning the mask and the wafer, and 15 includes a scanning velocity determination unit for determining a scanning velocity so as to maximize the number of wafer that can be exposed per unit time.